

**Amendments to the Claims:**

Claims 1 and 15 have been amended herein. Claims 14, 18 and 38 are canceled. New claims 46-59 are added. Please cancel claims 40 through 45, without prejudice to the filing of one or more divisional applications including same. Please note that all claims currently pending and under consideration in the referenced application are shown below. Please enter these claims as amended. This listing of claims will replace all prior versions and listings of claims in the application.

**Listing of Claims:**

1. (Currently Amended) A method of forming chip-scale packages, comprising;  
providing a semiconductor wafer having an active surface with a plurality of semiconductor die locations separated by at least one street of semiconductor material and having a passive surface opposite the active surface;  
cutting at least one channel in the active surface of the semiconductor wafer along the at least one street of semiconductor material to expose a plurality of semiconductor die side surfaces;  
etching the plurality of semiconductor die side surfaces to remove a layer of semiconductor material containing cutting-induced defects;  
forming a first protective coating on the semiconductor wafer to cover the active surface and fill the at least one channel;  
removing a layer of semiconductor material from the passive surface of the semiconductor wafer to a depth sufficient to expose the first protective coating within the at least one channel;  
and  
etching the passive surface of the semiconductor wafer such that the first protective coating exposed within the at least one channel forms at least one frame element protruding from the passive surface of the semiconductor wafer;  
forming a second protective coating on the semiconductor wafer to cover the passive surface;  
such that the second protective coating is anchored to the passive surface of the semiconductor wafer with the at least one frame element; and

separating the semiconductor wafer along the at least one channel to form a plurality of individual chip-scale packages.

2. (Original) The method of claim 1, wherein cutting at least one channel in the active surface of the semiconductor wafer comprises cutting the at least one channel with one of a dicing saw and a laser beam.

3. (Original) The method of claim 1, wherein forming the first protective coating on the semiconductor wafer comprises:  
applying a liquid polymer material over the active surface of the semiconductor wafer; and  
at least partially curing the liquid polymer material.

4. (Original) The method of claim 3, wherein applying the liquid polymer material comprises one of spraying or spin coating the liquid polymer material onto the active surface of the semiconductor wafer.

5. (Original) The method of claim 4, wherein each semiconductor die location of the plurality includes at least one bond pad, and further comprising:  
etching a portion of the first protective coating to expose the at least one bond pad of each semiconductor die location.

6. (Original) The method of claim 3, wherein the liquid polymer material comprises a photocurable liquid polymer material, and further comprising:  
exposing the photocurable liquid polymer material to a source of electromagnetic radiation to at least partially cure a portion of the photocurable liquid polymer material.

7. (Original) The method of claim 6, wherein each semiconductor die location of the plurality includes at least one bond pad, and further comprising:  
selectively curing the photocurable liquid polymer material to leave the at least one bond pad of each semiconductor die location exposed through the first protective coating.

8. (Original) The method of claim 1, wherein each semiconductor die location of the plurality includes at least one bond pad, and further comprising:  
forming a conductive bump on the at least one bond pad of each semiconductor die location.

9. (Original) The method of claim 8, wherein forming the conductive bump on the at least one bond pad comprises forming the conductive bump prior to forming the first protective coating on the semiconductor wafer.

10. (Original) The method of claim 9, wherein forming the first protective coating comprises:  
spraying or spin coating a liquid polymer material onto the active surface of the semiconductor wafer; and  
at least partially curing the liquid polymer material.

11. (Original) The method of claim 10, further comprising:  
etching a portion of the first protective coating to expose the conductive bump on the at least one bond pad of each semiconductor die location.

12. (Original) The method of claim 9, wherein forming the first protective coating comprises:  
applying a photocurable liquid polymer material over the active surface of the semiconductor wafer; and  
exposing the photocurable liquid polymer material to a source of electromagnetic radiation to at least partially cure a portion of the photocurable liquid polymer material.

13. (Original) The method of claim 12, further comprising:  
selectively curing the photocurable liquid polymer material to leave the conductive bump on the  
at least one bond pad of each semiconductor die location exposed through the first  
protective coating.

14. (Canceled)

15. (Currently Amended) The method of ~~claim 14~~ claim 1, wherein removing the  
layer of semiconductor material comprises planarizing the passive surface of the semiconductor  
wafer with at least one of a mechanical process and a chemical process.

16. (Original) The method of claim 15, wherein removing the layer of semiconductor  
material comprises backgrinding the passive surface of the semiconductor wafer.

17. (Original) The method of claim 15, wherein removing the layer of semiconductor  
material comprises a CMP process.

18. (Canceled)

19. (Original) The method of claim 1, wherein each semiconductor die location of the  
plurality of semiconductor die locations comprises a plurality of circuit layers extending a depth  
into the semiconductor wafer from the active surface of the semiconductor wafer, and wherein  
cutting at least one channel in the active surface of the semiconductor wafer comprises cutting  
the at least one channel to a depth that is greater than the depth of the circuit layers within the  
semiconductor wafer.

20. (Original) The method of claim 1, wherein etching the plurality of semiconductor die side surfaces comprises etching the plurality of semiconductor die side surfaces with an anisotropic etching process.

21. (Original) A method of forming chip-scale packages, comprising;  
providing a semiconductor wafer having an active surface with a plurality of semiconductor die locations separated by at least one street of semiconductor material;  
forming a first protective coating on the semiconductor wafer to cover the active surface;  
cutting at least one channel in a passive surface of the semiconductor wafer along the at least one street of semiconductor material to expose a plurality of semiconductor die side surfaces;  
etching the plurality of semiconductor die side surfaces to remove a layer of semiconductor material containing cutting-induced defects and to expose the first protective coating within the at least one channel;  
forming a second protective coating on the semiconductor wafer to cover the passive surface and fill the at least one channel; and  
separating the semiconductor wafer along the at least one channel to form a plurality of individual chip-scale packages.

22. (Original) The method of claim 21, wherein cutting at least one channel in the passive surface of the semiconductor wafer comprises cutting the at least one channel with one of a dicing saw and a laser beam.

23. (Original) The method of claim 21, wherein forming the first protective coating on the semiconductor wafer comprises:  
applying a liquid polymer material over the active surface of the semiconductor wafer; and  
at least partially curing the liquid polymer material.

24. (Original) The method of claim 23, wherein applying the liquid polymer material comprises one of spraying or spin coating the liquid polymer material onto the active surface of the semiconductor wafer.

25. (Original) The method of claim 24, wherein each semiconductor die location of the plurality includes at least one bond pad, and further comprising:  
etching a portion of the first protective coating to expose the at least one bond pad of each semiconductor die location.

26. (Original) The method of claim 23, wherein the liquid polymer material comprises a photocurable liquid polymer material, and further comprising:  
exposing the photocurable liquid polymer material to a source of electromagnetic radiation to at least partially cure a portion of the photocurable liquid polymer material.

27. (Original) The method of claim 26, wherein each semiconductor die location of the plurality includes at least one bond pad, and further comprising:  
selectively curing the photocurable liquid polymer material to leave the at least one bond pad of each semiconductor die location exposed through the first protective coating.

28. (Original) The method of claim 21, wherein each semiconductor die location of the plurality includes at least one bond pad, and further comprising:  
forming a conductive bump on the at least one bond pad.

29. (Original) The method of claim 28, wherein forming the conductive bump on the at least one bond pad comprises forming the conductive bump prior to forming the first protective coating on the semiconductor wafer.

30. (Original) The method of claim 29, wherein forming the first protective coating comprises:  
spraying or spin coating a liquid polymer material onto the active surface of the semiconductor wafer; and  
at least partially curing the liquid polymer material.

31. (Original) The method of claim 30, further comprising:  
etching a portion of the first protective coating to expose the conductive bump on the at least one bond pad of each semiconductor die location.

32. (Original) The method of claim 29, wherein forming the first protective coating comprises:  
applying a photocurable liquid polymer material over the active surface of the semiconductor wafer; and  
exposing the photocurable liquid polymer material to a source of electromagnetic radiation to at least partially cure a portion of the photocurable liquid polymer material.

33. (Original) The method of claim 32, further comprising:  
selectively curing the photocurable liquid polymer material to leave the conductive bump on the at least one bond pad of each semiconductor die location exposed through the first protective coating.

34. (Original) The method of claim 21, further comprising:  
removing a layer of semiconductor material from the passive surface of the semiconductor wafer prior to forming the second protective coating on the semiconductor wafer.

35. (Original) The method of claim 34, wherein removing the layer of semiconductor material comprises planarizing the passive surface of the semiconductor wafer with at least one of a mechanical process and a chemical process.

36. (Original) The method of claim 35, wherein removing the layer of semiconductor material comprises backgrinding the passive surface of the semiconductor wafer.

37. (Original) The method of claim 35, wherein removing the layer of semiconductor material comprises a CMP process.

38. (Canceled)

39. (Original) The method of claim 21, wherein etching the plurality of semiconductor die side surfaces comprises etching the plurality of semiconductor die side surfaces with an anisotropic etching process.

Claims 40-45 (Canceled)

46. (New) A method of forming chip-scale packages, comprising;  
providing a semiconductor wafer having an active surface with a plurality of semiconductor die locations separated by at least one street of semiconductor material;  
forming a first protective coating on the semiconductor wafer to cover the active surface;  
cutting at least one channel in a passive surface of the semiconductor wafer along the at least one street of semiconductor material to expose a plurality of semiconductor die side surfaces;  
etching the plurality of semiconductor die side surfaces to remove a layer of semiconductor material containing cutting-induced defects and to expose the first protective coating within the at least one channel;  
planarizing the passive surface of the semiconductor wafer with at least one of a mechanical process and a chemical process to remove a layer of semiconductor material from the passive surface of the semiconductor wafer, wherein planarizing and etching the plurality of semiconductor die side surfaces occur concurrently;  
forming a second protective coating on the semiconductor wafer after removing the layer of



semiconductor material to cover the passive surface and fill the at least one channel; and separating the semiconductor wafer along the at least one channel to form a plurality of individual chip-scale packages.

47. (New) The method of claim 46, wherein cutting at least one channel in the passive surface of the semiconductor wafer comprises cutting the at least one channel with one of a dicing saw and a laser beam.

48. (New) The method of claim 46, wherein forming the first protective coating on the semiconductor wafer comprises:  
applying a liquid polymer material over the active surface of the semiconductor wafer; and  
at least partially curing the liquid polymer material.

49. (New) The method of claim 48, wherein applying the liquid polymer material comprises one of spraying or spin coating the liquid polymer material onto the active surface of the semiconductor wafer.

50. (New) The method of claim 49, wherein each semiconductor die location of the plurality includes at least one bond pad, and further comprising:  
etching a portion of the first protective coating to expose the at least one bond pad of each semiconductor die location.

51. (New) The method of claim 48, wherein the liquid polymer material comprises a photocurable liquid polymer material, and further comprising:  
exposing the photocurable liquid polymer material to a source of electromagnetic radiation to at least partially cure a portion of the photocurable liquid polymer material.

52. (New) The method of claim 51, wherein each semiconductor die location of the plurality includes at least one bond pad, and further comprising:  
selectively curing the photocurable liquid polymer material to leave the at least one bond pad of each semiconductor die location exposed through the first protective coating.

53. (New) The method of claim 46, wherein each semiconductor die location of the plurality includes at least one bond pad, and further comprising:  
forming a conductive bump on the at least one bond pad.

54. (New) The method of claim 53, wherein forming the conductive bump on the at least one bond pad comprises forming the conductive bump prior to forming the first protective coating on the semiconductor wafer.

55. (New) The method of claim 54, wherein forming the first protective coating comprises:  
spraying or spin coating a liquid polymer material onto the active surface of the semiconductor wafer; and  
at least partially curing the liquid polymer material.

56. (New) The method of claim 55, further comprising:  
etching a portion of the first protective coating to expose the conductive bump on the at least one bond pad of each semiconductor die location.

57. (New) The method of claim 54, wherein forming the first protective coating comprises:  
applying a photocurable liquid polymer material over the active surface of the semiconductor wafer; and  
exposing the photocurable liquid polymer material to a source of electromagnetic radiation to at least partially cure a portion of the photocurable liquid polymer material.

58. (New) The method of claim 57, further comprising:  
selectively curing the photocurable liquid polymer material to leave the conductive bump on the  
at least one bond pad of each semiconductor die location exposed through the first  
protective coating.

59. (New) The method of claim 46, wherein etching the plurality of semiconductor  
die side surfaces comprises etching the plurality of semiconductor die side surfaces with an  
anisotropic etching process.